



SECOND SEMESTER M.Tech. (ME) DEGREE END SEMESTER EXAMINATION

APRIL 2018

SUBJECT: LOW POWER VLSI DESIGN (ECE - 5221)

TIME: 3 HOURS

MAX. MARKS: 50

Instructions to candidates

- Answer **ALL** questions.
- Missing data may be suitably assumed.

- 1A. Discuss the need for level converters in VLSI circuits and highlight the problems faced in using level converters in VLSI design. Also explain the ways to mitigate them.
- 1B. For a CMOS inverter a square waveform is fed at its input with rise and fall times of $t_r = 2$ ns and $t_f = 3$ ns. If $C_{ox} = 10$ fF/ μm^2 , calculate the average short circuit power dissipated. Assume that the short circuit current waveform is triangular, and flows for the entire duration of t_r and t_f .
- ($W_P/L_P = 4/0.5$ and $W_N/L_N = 2/0.5$, and operating with $V_{DD} = 3.3$ V. Assume $\mu_p = 130$ cm²/V.sec, $\mu_n = 545$ cm²/V-Sec. $V_{tn} = 0.8$ V, $V_{tp} = -0.8$ V.)
- 1C. List the factors that makes power an important design specification in VLSI.
- (5+3+2)
- 2A. With the help of suitable examples and HDL coding illustrate how dynamic power can be reduced in FSMs.
- 2B. With the help of an example explain bus segmentation for achieving low power and discuss its salient features.
- 2C. List the demerits of employing low swing buses in VLSI.
- (5+3+2)
- 3A. Discuss crosstalk in VLSI circuits and it's impact on the power dissipation and delay. Also, explain the techniques used to reduce crosstalk.
- 3B. Estimate the intrinsic wire delay of a Cu wire of length 10mm above a M1 ground plane with SiO₂ dielectric in 90nm CMOS technology, with thickness, width and height all equal to 6λ . Assume: $\rho = 30$ ohm-um, $c = 0.10$ fF/ μm . What will be the delay if a buffer with 200ps delay is inserted at the centre of the line? Calculate the optimum segment length needed for getting the optimum delay for a buffer delay of 200ps.
- 3C. List the process level techniques employed for leakage reduction.
- (5+3+2)

- 4A. Explain MTCMOS and VTCOMS techniques for reducing leakage power and compare them.
- 4B. The circuit shown in **Figure 4B**, is designed using 65nm CMOS technology using low threshold transistors. Each gate has a delay of 5ps and a leakage current of 10nA. Given that a gate with high threshold transistors has a delay of 10ps and leakage of 1nA, optimally design the circuit with dual-threshold gates to minimize the leakage current without increasing the critical path delay. What is the percentage reduction in leakage power? What will be the leakage power reduction if a 30% increase in the critical path delay is allowed? Calculate.
- 4C. Compare active leakage and standby leakage in VLSI circuits.
- 5A. Taking a low power processor or microcontroller as an example, explain the low power features and techniques employed in processor design.
- 5B. Discuss the adiabatic principle using suitable expressions. What are the merits and challenges involved in adiabatic logic? List and explain.
- 5C. List the salient features of predictive technique for dynamic power management.

(5+3+2)

(5+3+2)

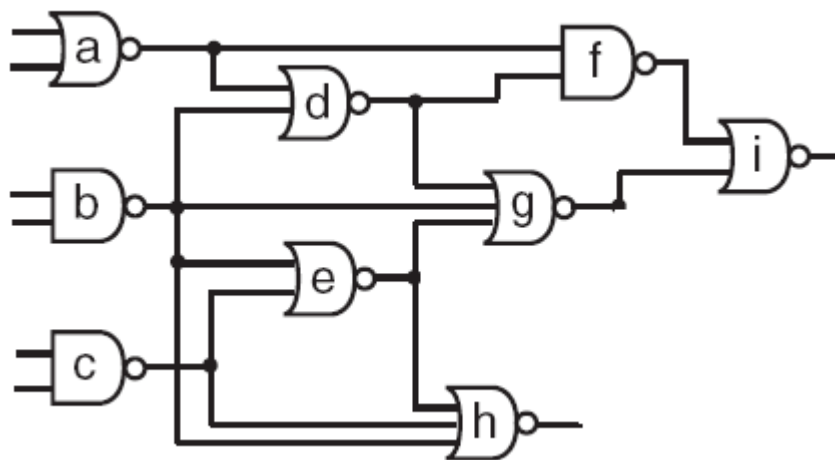


Figure 4B